

Supporting Information

Field Emission Behaviors of CsPbI₃ Nanobelts

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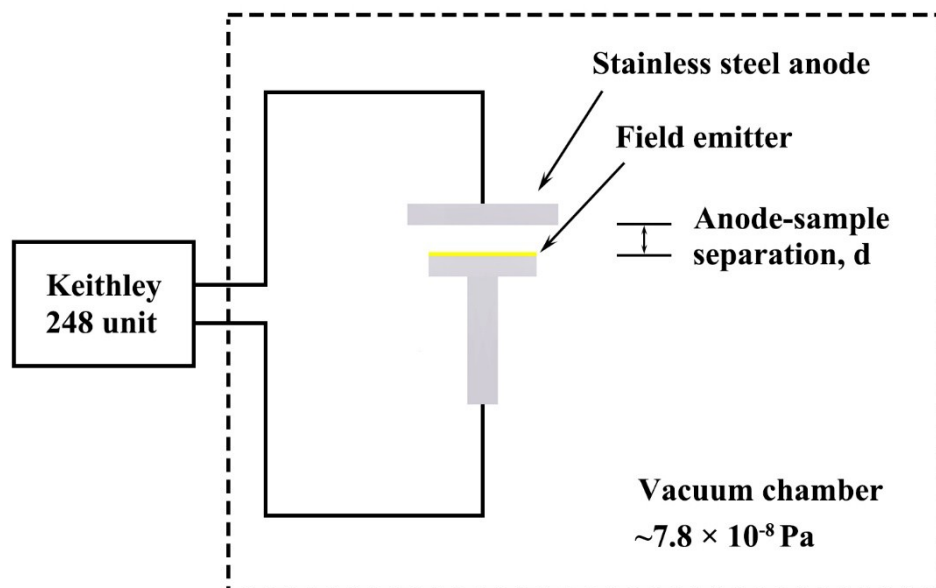


Fig. S1 Schematic diagram of the experimental setup used for measuring FE properties of CsPbI₃ nanobelts.

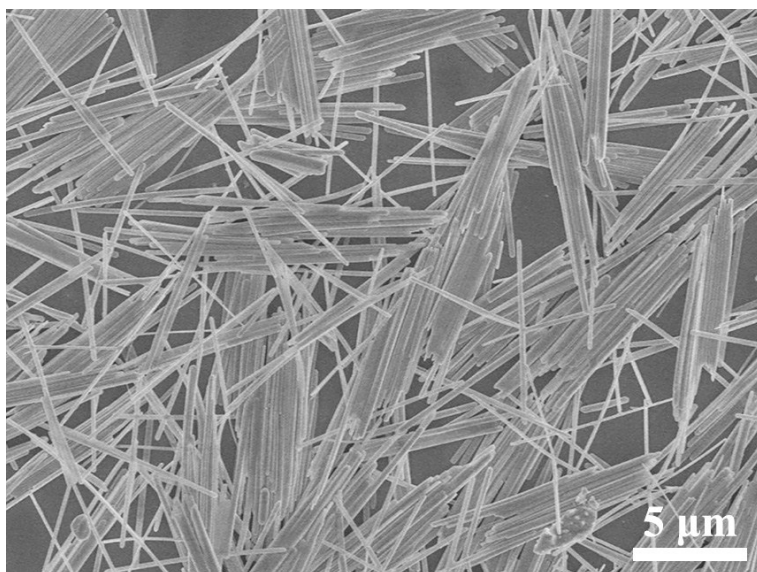


Fig. S2 Typical SEM image of the CsPbI₃ nanobelt emitter under a low magnification.

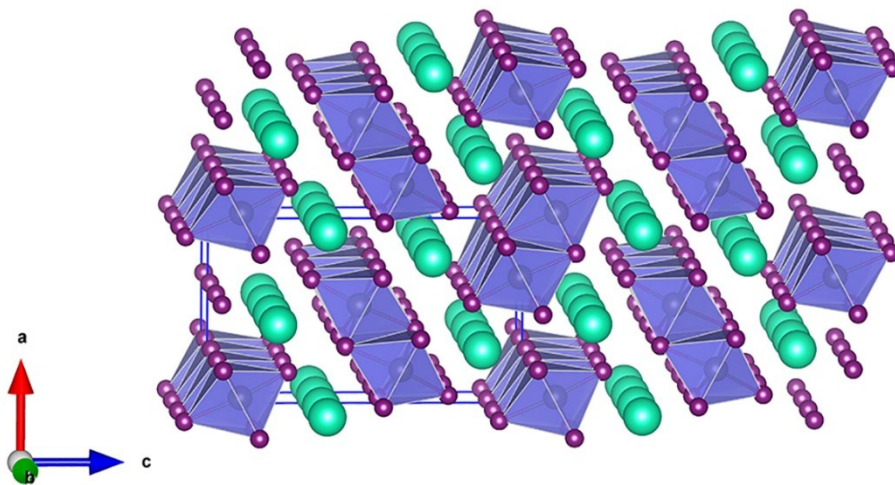


Fig. S3 The crystal structure of CsPbI₃ nanobelts.

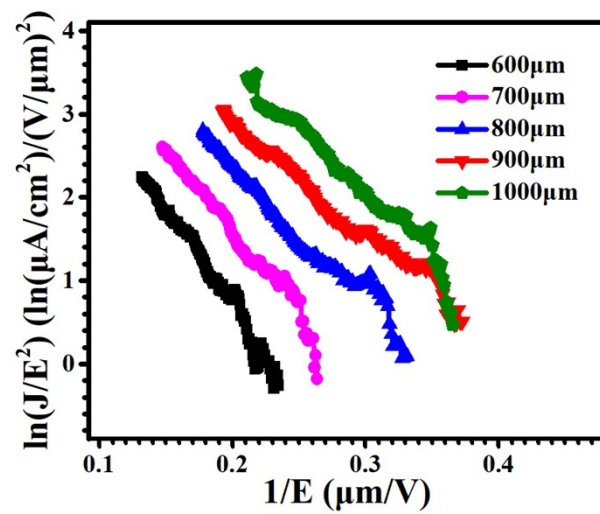


Fig. S4 *F-N* plots of CsPbI₃ nanobelt emitters with d fixed at 600-1000 μm with an interval of 100 μm .

Table S1 Turn-on fields (E_{to}) and β of typical semiconductor emitters ever reported.

Field emitters	E_{to} (V/μm)	β	Ref.
ZnS nanobelts	3.47	2010	1
AlN nanorod arrays	4.7	1888.7	2
Aligned AlN nanorods	3.8	950	3
CdS nanobelts	3.7	1298	4
CdS nanowire arrays	11.5	602	5
GaN nanocolumns	2.6	9725	6
Aligned ZnO nanobelts	1.3	14000	7
WO ₃ nanowires	4.8	-	8
MoS ₂ nanoflowers	4.5	-	9
SnO ₂ nanowires	3.5	1225	10
β -Ga ₂ O ₃ nanopillars	30	200	11
β -Ga ₂ O ₃ nanobelts	5.37	2242	12
SiC nanowires/nanorods	3.33	-	13
B-doped SiC nanowires	0.68	5464	14
Si nanowires	7.3	424	15
CsPbI ₃ nanorods	4	-	16
CsPbI ₃ rGO composite	2.5	11000	17
CH ₃ NH ₃ PbI _{3-x} Cl _x film	5.56	3183	17
CH ₃ NH ₃ PbI ₃ nanorods	4.2	-	18
CsPbI₃ nanobelts	2.62	3553	Our work

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